



SDI Review Form 1.6

Journal Name:	International Research Journal of Pure and Applied Chemistry
Manuscript Number:	2013_IRJPAC_8704
Title of the Manuscript:	The role of the etching rates in three-dimensional simulations of the profile evolution
Type of the Article	

General guideline for Peer Review process:

This journal's peer review policy states that **NO** manuscript should be rejected only on the basis of '**lack of Novelty**', provided the manuscript is scientifically robust and technically sound.

To know the complete guideline for Peer Review process, reviewers are requested to visit this link:

(<http://www.sciencedomain.org/page.php?id=sdi-general-editorial-policy#Peer-Review-Guideline>)



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PART 1: Review Comments

	Reviewer's comment	Author's comment <i>(if agreed with reviewer, correct the manuscript and highlight that part in the manuscript. It is mandatory that authors should write his/her feedback here)</i>
<u>Compulsory</u> REVISION comments	Abstract needs to be beefed up a little more. Tjis will enable any reader who picks up the abstract to see at once a summary of what you've done without referring to the main text. e.g. the influence of temperature and etchant concentration was considered. Results showed that increasing etchant concentration resuled in reduced etching rate while increasing etching temperature resulted in increased etching rate.	We agree. In accordance with the Referee's suggestion we re-write the abstract. All the Referee's comments were included in the revised manuscript. We would like to thank the Referee for help us to improve our manuscript.
<u>Minor</u> REVISION comments	Check some of your tenses.	We double checked the manuscript and removed typos.
<u>Optional/General</u> comments	It's a beautiful work and commended.	Thank you very much for the Referee's affirmative comments.